

**IN THE CLAIMS**

Please amend claim 1 as follows:

Sub  
C1  
B1  
1. (Twice Amended) A method of preventing generation of particles in a chamber, the method comprising:

mounting a substrate within a chamber of a gas-exposure equipment;

decreasing a pressure within the chamber;

injecting a surface treatment gas into the chamber, the surface treatment gas converting a surface of the substrate into an organic material; and

preventing moisture in air from penetrating into the chamber by drawing out the surface treatment gas from the chamber while injecting a nitrogen gas into the chamber.